

- [54] **LOW CONTACT ELECTRICAL RESISTANT COMPOSITION, SUBSTRATES COATED THEREWITH, AND PROCESS FOR PREPARING SUCH**
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- [58] Field of Search **428/698, 333, 469, 446; 204/192.14, 192.15, 192.17; 501/102, 134**

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ABSTRACT

A composition of a metallic compound represented by the formula MT, and G is provided by sputtering an M_xG_{100-x} target. M is a metal selected from the group of titanium, hafnium, zirconium, and mixtures thereof. T is selected from the group of N, C, and mixtures thereof. G is a metal selected from the group of gold, platinum, and palladium. X is an integer from about 65 to about 95. Also provided are substrates coated with the composition and process for depositing the composition on substrates.

20 Claims, 1 Drawing Sheet

